

***IN THE UNITED STATES PATENT AND TRADEMARK OFFICE***

**Applicant:** Koichi WATANABE et al.

**Title:** SPUTTERING TARGET AND PROCESS FOR PRODUCING Si  
OXIDE FILM THEREWITH

**Appl. No.:** Unassigned

**Filing Date:** 03/27/2006

**Examiner:** Unassigned

**Art Unit:** Unassigned

**PRELIMINARY AMENDMENT UNDER 37 CFR 1.115**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Prior to examination of the present Application, Applicants respectfully request that the application be amended as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this document.

**Remarks/Arguments** begin on page 4 of this document.

Please amend the application as follows: